



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: **Miwa KOZAWA et al.**

Serial No.: **10/670,291**

Group Art Unit: **2812**

Filed: **September 26, 2003**

Examiner: **Unassigned**

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR FORMING
RESIST PATTERN, AND PROCESS FOR MANUFACTURING
SEMICONDUCTOR DEVICE**

INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 CFR 1.97(b)(4)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

February 23, 2004

Sir:

The attention of the Patent and Trademark Office is hereby directed to the documents listed on the attached Form PTO-1449. One copy of each of these documents is attached along with a concise explanation of relevance continued in "Prior Art Information List."

No fee or certification is required in connection with this Information Disclosure Statement it is being submitted prior to the issuance of a first official action on the merits in the above-identified patent application.

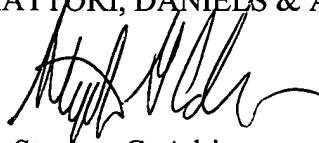
The above information is presented so that the Patent and Trademark Office can, in the first instance, determine any materiality thereof to the claimed invention. See 37 CFR 1.104(a) concerning the PTO duty to consider and use any such information. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the

documents cited in the attached Form PTO-1449 be made of record therein and appear on the first page of any patent to issue therefrom.

The Commissioner is authorized to charge our Deposit Account No. 50-2866 for any fee which is deemed by the Patent and Trademark Office to be required to effect consideration of this statement.

Respectfully submitted,

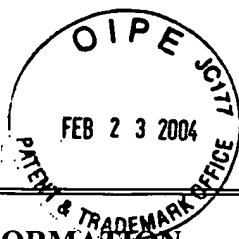
WESTERMAN, HATTORI, DANIELS & ADRIAN, LLP

A handwritten signature in black ink, appearing to read 'Stephen G. Adrian', is written over the printed name.

Stephen G. Adrian
Attorney for Applicants
Reg. No. 32,878

SGA/jnj

Enclosures: PTO-1449; Prior Art Information List and 4 references



INFORMATION DISCLOSURE STATEMENT PTO-1449	Attv. Docket No. 031181	Serial No. 10/670.291
	Applicant(s): Miwa KOZAWA et al.	
	Filing Date: September 26, 2003	Group Art Unit: 2812

U.S. PATENT DOCUMENTS

Examiner Initial		Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)

FOREIGN PATENT DOCUMENTS

Examiner Initial		Document	Date	Country	Translation (Yes – Abstract)
		10-73927	3/1998	Japan	Abstract
		5-197151	8/1993	Japan	Yes
		2000-347414	12/2000	Japan	Yes
		2001-228616	8/2001	Japan	Yes

OTHER DOCUMENTS

Examiner		Date Considered

PRIOR ART INFORMATION LIST

Your case No.	P7845-0698-031181
Our case No.	N-FT043-02P-US

Inventor, Patent Number, Country, Author, Title, Name of Document	Issue date	Concise Explanation of the Relevance (indication of page, column, line, figure of the relevant portion)
JP-A No. 10-73927	17/3/1998	Abstract
JP-A No. 5-197151	6/8/1993	<p>Cover page, Claims, [0001]~[0004], [0029]~[0052] and [0102]</p> <p>This publication is an invention disclosed for the purpose of forming a resist which adapts to plurality of exposure lights (exposure light wavelengths), and does not teach an idea of drawing fine patterns by irradiating plurality of exposure lights.</p>
JP-A No. 2000-347414	15/12/2000	<p>This publication discloses somewhat similar method to the present invention. However, the invention as disclosed in this publication differs in that the coat forming agent requires a water soluble nitrogen containing organic compound.</p> <p>Further, the term "coat forming agent for micro fabrication" according to this invention refers to micro fabrication in the hole patterns, and hence, it leads to increase the thickness of the resists.</p>
JP-A No. 2001-228616	24/8/2001	<p>The publication discloses an embodiment of thickening resist patterns. However, the publication does not focus on a resist pattern thickening of a resin substrate (alicyclic resist) developed for use in Arf Excimer Laser (wavelength 193 nm).</p>